

03400月00日11時04分 宛先:ADAMSON, WILKS 発信:セイコーインスツルメンツ(株) 知財財産部 108

ABSTRACT OF THE DISCLOSURE

A fine stencil structure correction device has a charged particle beam microscope lens-barrel which scans and corrects shapes of defect portions of a fine stencil structure sample using an etching or deposition function, and the fine stencil structure correction device further comprises transmitted beam detecting means for detecting a transmitted beam which is the charged particle beam penetrating the sample provided on a sample stage when the sample is scanned by the charged particle beam.